



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuyoshi TAMURA et al.

Group Art Unit: 1765

Application No.: 09/696,955

Examiner: M. A. Anderson

Filed: October 27, 2000

Docket No.: 107703

For: SILICON FOCUS RING AND METHOD FOR PRODUCING THE SAME

SUPPLEMENTAL AMENDMENT UNDER 37 CFR §1.114

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

As a Supplement to the December 2, 2002 filed Amendment, which is in reply to the June 12, 2002 Final Office Action, and in view of the attached Request for Continued Examination, the shortened statutory period for reply extended by the December 2, 2002 Petition for Extension of Time to December 12, 2002, please amend the above-identified application as follows:

IN THE CLAIMS:

Please add new claim 7 as follows:

--7. (New) The silicon focus ring according to Claim 3, wherein the etching treatment further comprises applying to the silicon focus ring one of either a mixed acid or an alkali aqueous solution. --

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